

TRADEMARK ASSIGNMENT

Electronic Version v1.1
 Stylesheet Version v1.1

SUBMISSION TYPE:	NEW ASSIGNMENT		
NATURE OF CONVEYANCE:	SECURITY INTEREST		
CONVEYING PARTY DATA			
Name	Formerly	Execution Date	Entity Type
Polyera Corporation		07/15/2011	CORPORATION: DELAWARE
RECEIVING PARTY DATA			
Name:	Solvay North America Investments, LLC		
Street Address:	3333 Richmond Ave.		
City:	Houston		
State/Country:	TEXAS		
Postal Code:	77098		
Entity Type:	LIMITED LIABILITY COMPANY: DELAWARE		
PROPERTY NUMBERS Total: 3			
Property Type	Number	Word Mark	
Registration Number:	3677029	ACTIVINK	
Registration Number:	3677030	ACTIVINKS	
Registration Number:	3677031	POLYERA	
CORRESPONDENCE DATA			
Fax Number:	(312)706-9000		
	<i>Correspondence will be sent via US Mail when the fax attempt is unsuccessful.</i>		
Phone:	3127018352		
Email:	zbeal@mayerbrown.com, ipdocket@mayerbrown.com		
Correspondent Name:	Erick J. Palmer		
Address Line 1:	P. O. Box 2828		
Address Line 4:	Chicago, ILLINOIS 606902828		
ATTORNEY DOCKET NUMBER:	10437752 EJP		
NAME OF SUBMITTER:	Erick J. Palmer		
Signature:	/ejp/		

OP \$90.00 3677029

900198136

TRADEMARK
 REEL: 004591 FRAME: 0768

Date:

07/27/2011

Total Attachments: 32

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INTELLECTUAL PROPERTY SECURITY AGREEMENT

This INTELLECTUAL PROPERTY SECURITY AGREEMENT (as amended, amended and restated, supplemented or otherwise modified from time to time, the “**IP Security Agreement**”) dated July 15, 2011, is made by POLYERA CORPORATION, a Delaware corporation (the “**Grantor**”) in favor of SOLVAY NORTH AMERICA INVESTMENTS, LLC, a Delaware limited liability company and any other entity or person set forth on the signature page hereto who has been issued Notes (collectively, the “**Lender**”). Capitalized terms used herein and not otherwise defined herein shall have the meanings assigned to such terms in Exhibit A attached hereto or the Security Agreement (as defined below), as applicable.

WHEREAS, pursuant to the Security Agreement dated as of even date herewith (as amended, restated, amended and restated, supplemented, waived or otherwise modified or replaced from time to time, the “**Security Agreement**”), by and between the Grantor and the Lender, the Grantor has granted to the Lender a first priority security interest in order to support certain obligations of the Grantor owed to the Lender under the terms of the Notes.

WHEREAS, pursuant to the Security Agreement, the Grantor has granted to the Lender a first priority security interest in all personal property of the Grantor, including all Intellectual Property of the Grantor as hereafter defined, including without limitation, all Trademarks, Patents, Copyrights, Trade Secrets and IP Agreements, as hereafter defined, all to secure the payment and performance of the Obligations (as defined in the Security Agreement).

WHEREAS, in order to evidence such security interest and to perfect the Lender’s rights in such Intellectual Property, the Grantor has agreed to execute this IP Security Agreement for recording with the U.S. Patent and Trademark Office, the United States Copyright Office and other governmental authorities and agrees to execute any additional documents as necessary to record such security interest with the U.S. Patent and Trademark Office, U.S. Copyright Office or other governmental authorities.

NOW, THEREFORE, for and in consideration of the premises, and for good and valuable consideration, the receipt and sufficiency of which are hereby acknowledged, the Grantor agrees as follows:

SECTION 1. Grant of Security. The Grantor hereby grants to the Lender a first priority security interest in all of such Grantor’s right, title and interest, whether now owned or existing or hereafter created, acquired or arising, in and to the following (the “**Collateral**”):

- (a) all Patents, in each case now existing or hereafter adopted or acquired, including those set forth in Schedule A hereto;
- (b) all Trademarks, in each case now existing or hereafter adopted or acquired, including those set forth in Schedule A hereto; and
- (c) all Copyrights, in each case now existing or hereafter adopted or acquired, including those set forth in Schedule A hereto.

SECTION 2. Recordation. This IP Security Agreement has been executed and delivered by the Grantor for the purpose of recording the grant of security interest herein with the United States Patent and Trademark Office and the United States Copyright Office, or other governmental agency. The Grantor authorizes and requests that the Register of Copyrights, the Commissioner for Patents and the Commissioner for Trademarks record this IP Security Agreement.

SECTION 3. Representations, Warranties And Covenants. Grantor represents, warrants and covenants that: (i) Schedule A sets forth a true and complete list of all Patent, Trademark and Copyright registrations and pending applications now owned, licensed, controlled or used by the Grantor; (ii) the Intellectual Property, including such Patent, Trademark and Copyright applications and registrations set forth on Schedule A, are subsisting and have not been adjudged invalid or unenforceable, in whole or in part, and there is no litigation or proceeding pending concerning the validity or enforceability of the Intellectual Property or Grantor's ownership rights therein; (iii) to the best of Grantor's knowledge, each of the Intellectual Property is valid and enforceable; (iv) to the best of Grantor's knowledge, there is no infringement by a third party of the Intellectual Property; (v) no claim has been made that the use of any of the Intellectual Property does or may violate the rights of any third person, and to the best of Grantor's knowledge, there is no infringement by Grantor of the intellectual property rights of others; (vi) Grantor is the sole and exclusive owner of the entire and unencumbered right, title and interest in and to each of the Intellectual Property free and clear of any liens, charges, encumbrances and adverse claims, including pledges, assignments, licenses, registered user agreements and covenants by Grantor not to sue third persons, other than the security interest and assignment created by the Security Agreement and this IP Security Agreement; (vii) Grantor has the unqualified right to enter into this IP Security Agreement and to perform its terms and has entered and will enter into written agreements with each of its present and future employees, agents, consultants, licensors and licensees that will enable them to comply with the covenants herein contained; (viii) Grantor has used, and will continue to use, proper statutory and other appropriate proprietary notices in connection with its use of the Patents, Trademarks or Copyrights; and (ix) Grantor has used, and will continue to use for the duration of this IP Security Agreement, consistent standards of quality in its manufacture and provision of products and services sold or provided under the Trademarks.

SECTION 4. No Transfer Or Inconsistent Agreements. Without the Lender's prior written consent, Grantor will not (i) mortgage, pledge, assign, encumber, grant a security interest in, transfer, license or alienate any of the Intellectual Property or (ii) enter into any agreement that is inconsistent with the Grantor's obligations under this IP Security Agreement or the Security Agreement.

SECTION 5. After-Acquired Intellectual Property.

5.1 After-Acquired Intellectual Property. If, before the Obligations shall have been finally paid and satisfied in full, Grantor obtains any right, title or interest in or to any other or new Intellectual Property, the provisions of this IP Security Agreement shall automatically apply thereto and Grantor shall promptly provide to the Lender notice thereof in writing and execute and deliver to the Lender such documents or instruments as the Lender may reasonably request further to implement, preserve or evidence the Lender's interest therein

5.2 Amendment to Schedule. Grantor authorizes the Lender to modify this Intellectual Property Agreement, without the necessity of the Grantor's further approval or signature, by amending Exhibit A hereto to include any future or other Patent, Trademark or Copyright registrations or applications.

SECTION 6. Execution in Counterparts. This IP Security Agreement may be executed in any number of counterparts, each of which when so executed shall be deemed to be an original and all of which taken together shall constitute one and the same agreement.

SECTION 7. Grants, Rights and Remedies. This IP Security Agreement has been entered into in conjunction with the provisions of the Security Agreement. The Grantor does hereby acknowledge and confirm that the grant of the security interest hereunder to, and the rights and remedies of, the Lender with respect to the Collateral are more fully set forth in the Security Agreement, the terms and provisions of which are incorporated herein by reference as if fully set forth herein. In the event of any conflict between the terms of this IP Security Agreement and the terms of the Security Agreement, the terms of the Security Agreement shall govern.

SECTION 8. Governing Law. THIS IP SECURITY AGREEMENT AND THE RIGHTS AND OBLIGATIONS OF THE PARTIES UNDER THIS IP SECURITY AGREEMENT AND ALL CLAIMS RELATING TO THE SUBJECT MATTER HEREOF, WHETHER SOUNDING IN CONTRACT LAW OR TORT LAW, SHALL BE CONSTRUED IN ACCORDANCE WITH AND GOVERNED BY THE LAWS OF THE STATE OF DELAWARE.

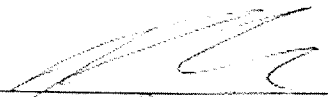
SECTION 9. Severability. In case any one or more of the provisions contained in this IP Security Agreement should be held invalid, illegal or unenforceable in any respect, the validity, legality and enforceability of the remaining provisions contained herein and in the Security Agreement shall not in any way be affected or impaired thereby (it being understood that the invalidity of a particular provision in a particular jurisdiction shall not in and of itself affect the validity of such provision in any other jurisdiction). The parties hereto shall endeavor in good-faith negotiations to replace the invalid, illegal or unenforceable provisions with valid provisions the economic effect of which comes as close as possible to that of the invalid, illegal or unenforceable provisions.

SECTION 10. Termination. This IP Security Agreement shall terminate upon the earlier of (i) the repayment in full of all outstanding Obligations and (ii) the agreement of both the Grantor and the Lender.

* Remainder of Page Intentionally Blank *

IN WITNESS WHEREOF, the Grantor has caused this IP Security Agreement to be duly executed and delivered by its officer thereunto duly authorized as of the date first above written.

POLYERA CORPORATION, as Grantor


By: 
Name: P. INAGARTZ
Title: CEO

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

TRADEMARK
REEL: 004591 FRAME: 0773

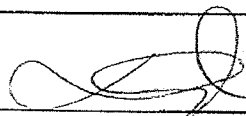
Accepted and Agreed to:

SOLVAY NORTH AMERICA INVESTMENTS,
LLC, as Lender

By: 
Name: _____
Title: _____

LENDER:

Léopold Demiddeleer
Sr Exec VP
Solvay Future Businesses

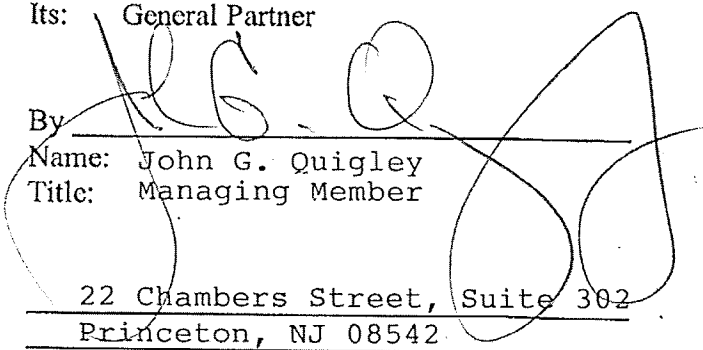
By: 
Print Name: DAVID C. SZEJDEK
Title: _____

Address: 16725 DANE COURT West
BROOKFIELD WI
53005

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

QFP, LP

By: QFP Management Company
Its: General Partner

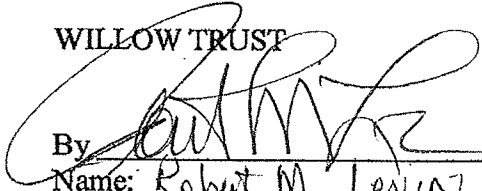
By: 
Name: John G. Quigley
Title: Managing Member

Address: 22 Chambers Street, Suite 302
Princeton, NJ 08542

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

TRADEMARK
REEL: 004591 FRAME: 0776

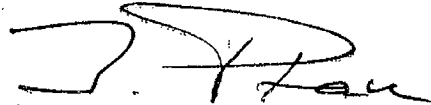
WILLOW TRUST

By 
Name: Robert M. Lewin
Title: Trustee

Address: _____

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

TRADEMARK
REEL: 004591 FRAME: 0777



Jean Pfau

Address:

Grietzenstrasse 1

8807 FREIENBACH

SWITZERLAND

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

TRADEMARK
REEL: 004591 FRAME: 0778

By: *Michael J. Treble*
Print Name: Michael J. Treble
Title: _____

Address: 4848 Esplanade St
Bonita Springs, FL
34134

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

RALF SCHERSCHMIDT


By: Ralf A Scherschmidt
Print Name: ✓RALF SCHERSCHMIDT
Title: _____

Address: 3312 N CLIFTON AVE #1
CHICAGO, IL 60657

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

TRADEMARK
REEL: 004591 FRAME: 0780

ED ZSCHAU ENTERPRISES

By 
Name: ED ZSCHAU
Title: OWNER

Address: PO Box 7391
MENLO PARK, CA 94026

By: [Signature]
Print Name: KURT E HOLSTEN
Title: Manager

Address: 17001 Collins Ave #4608
Sunny Isles, FL
33160

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

R CAPITAL MURDOCK PARTNERS, LLC

By: Sean J. Murdock
Print Name: SEAN J MURDOCK
Title: VICE PRESIDENT

Address: _____

SIGNATURE PAGE TO
IP SECURITY AGREEMENT

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Exhibit A
Additional Definitions

“**Copyrights**” means all of the following: (a) all copyright rights in any work subject to the copyright laws of the United States or any other country or group of countries, whether as author, assignee, transferee or otherwise including but not limited to copyrights in software and all rights in and to databases, all designs (including but not limited to industrial designs, Protected Designs within the meaning of 17 U.S.C. 1301 et. seq. and European Community designs), and all Mask Works (as defined under 17 U.S.C. 901 of the U.S. Copyright Act), whether registered or unregistered, and (b) all registrations and applications for registration of any such copyright in the United States or any other country or group of countries, including registrations, supplemental registrations and pending applications for registration in the United States Copyright Office listed on Schedule A and (c) all proceeds of and the right to sue or otherwise recover for any past, present and future infringement or other violation thereof, or enforcement of any Copyright.

“**General Intangibles**” means all “General Intangibles” as defined in the UCC, including all choses in action and causes of action and all other intangible personal property of any Grantor of every kind and nature (other than accounts (as defined in the UCC)) now owned or hereafter acquired by any Grantor, including corporate or other business records, indemnification claims, contract rights (including rights under leases, whether entered into as lessor or lessee, and other agreements), Intellectual Property, goodwill, registrations, franchises and tax refund claims.

“**Intellectual Property**” means all Patents, Copyrights, Trademarks, IP Agreements, Trade Secrets, domain names, and all inventions, designs, confidential or proprietary technical and business information, know-how, show-how and other proprietary data or information and all related documentation.

“**IP Agreements**” means all agreements granting to or receiving from a third party any rights to Intellectual Property to which any Grantor, now or hereafter, is a party.

“**Patents**” means all of the following: (a) all letters patent of the United States or the equivalent thereof in any other country or group of countries, and all applications for letters patent of the United States or the equivalent thereof in any other country or group of countries, including those listed on Schedule A, (b) all reissues, continuations, divisions, provisionals, continuations-in-part or extensions thereof, and the inventions disclosed or claimed therein, including the right to make, use and/or sell the inventions disclosed or claimed therein and (c) all proceeds of and the right to sue or otherwise recover for any past, present and future infringement or other violation thereof, or for enforcement of any Patent.

“**Trademarks**” means all of the following: (a) all domestic and foreign trademarks, trade names, service marks, corporate names, company names, business names, fictitious business names, trade styles, trade dress, logos, service marks, other source or business identifiers, designs and General Intangibles of like nature, now owned or hereafter adopted or acquired, all registrations thereof, if any, including all registration and recording applications filed in connection therewith in the United States Patent and Trademark Office listed on Schedule A and all renewals thereof, including those listed on Schedule A (provided that no security interest shall

be granted in United States intent-to-use trademark applications to the extent that, and solely during the period, if any, in which, the grant of a security interest therein would impair the validity or enforceability of such intent-to-use trademark applications under applicable federal law), (b) all goodwill associated therewith or symbolized thereby and (c) all proceeds of, and the right to sue or otherwise recover for any past, present and future infringement, dilution or other violation of any of the foregoing or for any injury to the related goodwill associated with the use of any Trademark or for enforcement of any Trademark.

“Trade Secrets” means common law and statutory trade secrets and all other confidential or proprietary or useful information and all know-how obtained by or used in or contemplated at any time for use in the business of any Grantor (all of the foregoing being collectively called a **“Trade Secret”**), whether or not such Trade Secret has been reduced to a writing or other tangible form, including all documents and things embodying, incorporating or referring in any way to such Trade Secret, all Trade Secret licenses, and including the right to sue for and to enjoin and to collect damages for the actual or threatened misappropriation of any Trade Secret and for the breach or enforcement of any such Trade Secret license.

[End of Exhibit A]

Schedule A
Intellectual Property

Patents

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-003	ORGANIC SEMICONDUCTOR MATERIALS AND METHODS OF PREPARING AND USE THEREOF - Marks et al.						
	US	11/977,418	7,947,837	10/24/07	05/24/2011	Issued	Polyera only
PF62173	EP	07852913.8	EP2089398	10/24/07	08/19/2009	Pending	Polyera only
	PCT	PCT/US07/22506	WO08/51552	10/24/07	05/02/2008	Nationalized	Polyera only
	USPR	60/854,345	-----	10/25/06	-----	Expired	Polyera only
POL-004	ACENE-BASED ORGANIC SEMICONDUCTOR MATERIALS AND METHODS OF PREPARING AND USE THEREOF - Facchetti et al.						
	US	11/986,017	7,892,454	11/19/07	02/22/2011	Issued	Polyera and Northwestern University
	PCT	PCT/US07/24118	WO08/63583	11/19/07	05/29/2008	Abandoned	Polyera and Northwestern University
	USPR	60/859,641	-----	11/17/06	-----	Expired	Polyera and Northwestern University
POL-005	PHOTOPOLYMER-BASED DIELECTRIC MATERIALS AND METHODS OF MANUFACTURING AND USE THEREOF - Yan et al.						
	US	11/998,159	7,981,989	11/28/07	07/19/2011	Issued	Polyera only
	EP	07862266.9	EP2089442	11/28/07	08/19/2009	Pending	Polyera only
	JP	2009-539298	2010-511094	11/28/07	04/08/2010	Pending	Polyera only
	PCT	PCT/US07/24473	WO08/66826	11/28/07	06/05/2008	Nationalized	Polyera only
	USPR	60/861,308	-----	11/28/06	-----	Expired	Polyera only
POL-006	RYLENE-BASED ORGANIC SEMICONDUCTOR MATERIALS AND METHODS OF PREPARING AND USE THEREOF - Facchetti et al.						
	US	11/986,019	7,902,363	11/19/07	03/08/2011	Issued	Polyera only
PF62175	EP	07862121.6	EP2086974	11/19/07	08/12/2009	Pending	Polyera only
PF62175	JP	2009-537237	-----	11/19/07	-----	Pending	Polyera only
	PCT	PCT/US07/24189	WO08/63609	11/19/07	09/12/2008	Nationalized	Polyera only
	USPR	60/859,761	-----	11/17/06	-----	Expired	Polyera only

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-007							
ORGANIC SEMICONDUCTOR MATERIALS AND PRECURSORS THEREOF - Facchetti et al.							
	US	12/011,030		01/23/08		Allowed	Polyera only
	PCT	PCT/US08/00942	WO08/91670	01/23/08	07/31/2008	Abandoned	Polyera only
	USPR	60/897,257		01/24/07		Expired	Polyera only
POL-008							
METHODS FOR PREPARING ARENE-BIS(DICARBOXIMIDE)-BASED SEMICONDUCTING MATERIALS AND RELATED INTERMEDIATES FOR PREPARING SAME - Facchetti et al.							
	US	12/006,934	7,893,265	01/07/08	02/22/2011	Issued	Polyera only
PF62333	CN	200880007028.0	CN101622253	01/07/08	01/06/2010	Pending	Polyera only
PF62333	EP	08724424.0	EP2104676	01/07/08	09/30/2009	Pending	Polyera only
PF62333	JP	2009-544945		01/07/08		Pending	Polyera only
PF62333	KR	10-2009-7016581		01/07/08		Pending	Polyera only
	PCT	PCT/US08/00194	WO08/85942	01/07/08	07/17/2008	Nationalized	Polyera only
	USPR	60/879,145		01/08/07		Expired	Polyera only
POL-009B							
SEMICONDUCTOR MATERIALS PREPARED FROM RYLENE (PI-ACCEPTOR) COPOLYMERS - Facchetti et al.							
PF60552	US	12/865,031	2011-0120558	02/05/09	05/26/2011	Pending	Polyera and BASF
PF60552	CN			02/05/09		Pending	Polyera and BASF
PF60552	EP	09707540.2	EP2240528	02/05/09	10/20/2010	Pending	Polyera and BASF
PF60552	IN					Pending	Polyera and BASF
PF60552	JP	2009-544945		02/05/09		Pending	Polyera and BASF
PF60552	KR	10-2009-7016581		02/05/09		Pending	Polyera and BASF
PF60552	TW	098103773		02/05/09		Pending	Polyera and BASF
PF60552	CA			02/05/09		Abandoned	Polyera and BASF
PF60552	MY			02/05/09		Abandoned	Polyera and BASF
PF60552	SG			02/05/09		Abandoned	Polyera and BASF
PF60552	PCT	PCT/EP09/51315	WO2009/098254	02/05/09	08/13/2009	Nationalized	Polyera and BASF
PF60552	USPR	61/026,322		02/05/08		Expired	Polyera and BASF
PF60552	USPR	61/088,236		08/12/08		Expired	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-010B							
PERYLENE SEMICONDUCTORS AND METHODS OF PREPARATION AND USE THEREOF - Kastler et al.							
PF60551	US	12/866,331	2010-0319778	02/05/09	12/23/2010	Pending	Polyera and BASF
PF60551	CN			02/05/09		Pending	Polyera and BASF
PF60551	EP	09709379.3	EP2240970	02/05/09	10/20/2010	Pending	Polyera and BASF
PF60551	IN					Pending	Polyera and BASF
PF60551	JP	2010-545463		02/05/09		Pending	Polyera and BASF
PF60551	KR	10-2010-7018813		02/05/09		Pending	Polyera and BASF
PF60551	TW	098103786		02/05/09		Pending	Polyera and BASF
PF60551	CA			02/05/09		Abandoned	Polyera and BASF
PF60551	MY			02/05/09		Abandoned	Polyera and BASF
PF60551	SG			02/05/09		Abandoned	Polyera and BASF
PF60551	PCT	PCT/EP09/51313	WO2009/098252	02/05/09	08/13/2009	Nationalized	Polyera and BASF
PF60551	USPR	61/026,311		02/05/08		Expired	Polyera and BASF

POL-015B							
RYLENE-BASED SEMICONDUCTOR MATERIALS AND METHODS OF PREPARATION AND USE THEREOF - Facchetti et al.							
PF60902	US			05/29/09		Pending	Polyera and BASF
PF60902	CN			05/29/09		Pending	Polyera and BASF
PF60902	EP	09753957	EP2313409	05/29/09	03/25/2011	Pending	Polyera and BASF
PF60902	JP			05/29/09		Pending	Polyera and BASF
PF60902	KR			05/29/09		Pending	Polyera and BASF
PF60902	TW	098117835		05/25/09			
PF60902	TW	098118110		05/28/09		Pending	Polyera and BASF
PF60902	CA			05/29/09		Abandoned	Polyera and BASF
PF60902	IN			05/29/09		Abandoned	Polyera and BASF
PF60902	MY			05/29/09		Abandoned	Polyera and BASF
PF60902	SG			05/29/09		Abandoned	Polyera and BASF
PF60902	PCT	PCT/EP09/56338	WO2009/144205	05/26/09	12/03/2009	Nationalized	Polyera and BASF
PF60902	PCT	PCT/EP09/56624	WO2009/144302	05/29/09	12/03/2009	Nationalized	Polyera and BASF
PF60902	USPR	61/057,547		05/30/08		Expired	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-016B							
NAPHTHALENE-IMIDE SEMICONDUCTOR POLYMERS - Facchetti et al.							
PF61119	US	12,865,964	2010-0326527	02/05/09	12/30/2010	Pending	Polyera and BASF
PF61119	CN			02/05/09		Pending	Polyera and BASF
PF61119	EP	09707663.2	EP2240529	02/05/09	10/20/2010	Pending	Polyera and BASF
PF61119	IN					Pending	Polyera and BASF
PF61119	JP	2010-545463		02/05/09		Pending	Polyera and BASF
PF61119	KR	10-2010-7018813		02/05/09		Pending	Polyera and BASF
PF61119	TW	098103780		02/05/09		Pending	Polyera and BASF
PF61119	CA			02/05/09		Abandoned	Polyera and BASF
PF61119	MY			02/05/09		Abandoned	Polyera and BASF
PF61119	SG			02/05/09		Abandoned	Polyera and BASF
PF61119	PCT	PCT/EP09/51314	WO2009/098253	02/05/09	08/13/2009	Nationalized	Polyera and BASF
PF61119	USPR	61/050,010		05/02/08		Expired	Polyera and BASF
PF61119	USPR	61/088,246		08/12/08		Expired	Polyera and BASF
PF61119	USPR	61/112,478		11/07/08		Expired	Polyera and BASF
POL-018B							
PHOTOCURABLE POLYMER DIELECTRICS AND METHODS OF PREPARATION AND USE THEREOF - Quinn et al.							
PF61454	US			11/20/09		Pending	Polyera and BASF
PF61454	CN			11/20/09		Pending	Polyera and BASF
PF61454	EP			11/20/09		Pending	Polyera and BASF
PF61454	JP			11/20/09		Pending	Polyera and BASF
PF61454	KR			11/20/09		Pending	Polyera and BASF
PF61454	TW	098139975		11/20/09		Pending	Polyera and BASF
PF61454	PCT	PCT/EP09/65569	WO2010/057984	11/20/09	05/27/2010	Nationalized	Polyera and BASF
PF61454	USPR	61/117,404		11/24/08		Expired	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-019B							
PERYLENE-IMIDE SEMICONDUCTOR POLYMERS - Facchetti et al.							
PF61117	US	12/812,531	2010-0283047	02/05/09	11/11/2010	Pending	Polyera and BASF
PF61117	EP	09708280.4	EP2240530	02/05/09	10/20/2010	Pending	Polyera and BASF
PF61117	CA			02/05/09		Abandoned	Polyera and BASF
PF61117	CN			02/05/09		Abandoned	Polyera and BASF
PF61117	IN			02/05/09		Abandoned	Polyera and BASF
PF61117	JP			02/05/09		Abandoned	Polyera and BASF
PF61117	KR			02/05/09		Abandoned	Polyera and BASF
PF61117	MY			02/05/09		Abandoned	Polyera and BASF
PF61117	SG			02/05/09		Abandoned	Polyera and BASF
PF61117	TW	098103783		02/05/09		Abandoned	Polyera and BASF
PF61117	PCT	PCT/EP09/51311	WO2009/098250	02/05/09	08/13/2009	Nationalized	Polyera and BASF
PF61117	USPR	61/088,215		08/12/08		Expired	Polyera and BASF
POL-020							
CONJUGATED POLYMERS AND THEIR USE IN OPTOELECTRONIC DEVICES - Pan et al.							
	PCT	PCT/US10/35878		05/21/10		Pending	Polyera only
	USPR	61/180,256		05/21/09		Expired	Polyera only
POL-021							
SEMICONDUCTING COMPOUNDS AND DEVICES INCORPORATING SAME							
	US	12/755,308	2010/0252112	04/06/2010	10/07/2010	Pending	U. of Kentucky Research Foundation
	PCT	PCT/US10/001038	WO2010/117449	04/06/2010	10/14/2010	Pending	U. of Kentucky Research Foundation
	USPR	61/166,896		04/06/2009		Expired	U. of Kentucky Research Foundation
POL-022							
ORGANIC SEMICONDUCTORS AND DEVICES INCORPORATING SAME - Quinn et al.							
	US	12/980,936		12/29/10		Pending	Polyera only
	PCT	PCT/US10/62365		12/29/10		Pending	Polyera only
	USPR	61/290,676		12/29/09		Expired	Polyera only

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-023		DIELECTRIC MATERIALS AND METHODS OF PREPARATION AND USE THEREOF - Zheng et al.					
	US	13/007,148		01/14/11		Pending	Polyera only
	PCT	PCT/US11/21332		01/14/11		Pending	Polyera only
	USPR	61/295,725		01/17/10		Expired	Polyera only
POL-024		PYRROLO[3,2-B]PYRROLE SEMICONDUCTING COMPOUNDS AND DEVICES INCORPORATING SAME - Lu et al.					
	US	13/032,055		03/19/11		Pending	Polyera only
	PCT	PCT/US11/29112		03/19/11		Pending	Polyera only
	USPR	61/315,911		03/20/10		Expired	Polyera only
POL-025		CONJUGATED POLYMERS AND THEIR USE IN OPTOELECTRONIC DEVICES - Zhu et al.					
	US	12/785,357	2010/0307594	05/21/10	12/09/2010	Pending	Polyera only
	TW	99116343		05/21/10		Pending	Polyera only
	PCT	PCT/US10/35850	WO2010/135701	05/21/10	11/25/2010	Pending	Polyera only
	USPR	61/323,152		04/12/10		Expired	Polyera only
POL-026		SEMICONDUCTING COMPOUNDS AND RELATED COMPOSITIONS AND DEVICES - Facchetti et al.					
	USPR	61/377,964		08/29/10		Pending	Polyera only
POL-027		POLYCYCLIC AROMATIC MOLECULAR SEMICONDUCTORS AND RELATED COMPOSITIONS AND DEVICES - Facchetti et al.					
	USPR	61/387,643		09/29/10		Pending	Polyera only
POL-028		CONJUGATED POLYMERS AND THEIR USE IN OPTOELECTRONIC DEVICES - Zhu et al.					
	USPR	61/405,870		10/22/10		Pending	Polyera only

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-029							POLYCYCLIC AROMATIC MOLECULAR SEMICONDUCTORS AND RELATED COMPOSITIONS AND DEVICES – Chen et al.
	USPR	61/390,402		10/06/10		Pending	Polyera and M.C. Chen
POL-030							CONJUGATED POLYMERS AND THEIR USE IN OPTOELECTRONIC DEVICES – Pan et al.
	USPR	61/416,890		11/24/10		Pending	Polyera only
POL-032							HETEROAROMATIC SEMICONDUCTING POLYMERS – Facchetti
	USPR	61/444,920		02/21/11		Pending	Polyera only
POL-033							NAPHTHOBISTHIAZOLE POLYMERS FOR USE IN ORGANIC SEMICONDUCTOR DEVICES – Quinn et al.
	USPR	61/449,894		03/07/11		Pending	Polyera only
POL-034							CARBONACEOUS NANOMATERIAL-BASED THIN FILM TRANSISTORS – Xia et al.
	USPR	61/487,931		05/19/11		Pending	Polyera only
POL-200B							ORGANIC SEMICONDUCTING POLYMERS – Facchetti
	US	13/128,214		11/06/09	11/11/2010	Pending	Polyera and BASF
	TW	098137899		11/06/09		Pending	Polyera and BASF
	PCT	PCT/EP09/64722	WO2009/098250	11/06/09	05/14/2010	Nationalized	Polyera and BASF
PF61407	USPR	61/112,492		11/07/08		Expired	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-201B SEMICONDUCTOR MATERIALS PREPARED FROM DITHIENYL VINYLENE COPOLYMERS – <i>Mishra et al.</i>							
PF61582	US			12/16/09		Pending	Polyera and BASF
PF61582	EP	09169242.6		09/02/09		Pending	Polyera and BASF
PF61582	CN			12/16/09		Pending	Polyera and BASF
PF61582	IN			12/16/09		Pending	Polyera and BASF
PF61582	JP			12/16/09		Pending	Polyera and BASF
PF61582	KR			12/16/09		Pending	Polyera and BASF
PF61582	TW	098143766		12/16/09		Pending	Polyera and BASF
PF61582	CA			12/16/09		Filed?	Polyera and BASF
PF61582	MY			12/16/09		Filed?	Polyera and BASF
PF61582	SG			12/16/09		Filed?	Polyera and BASF
PF61582	PCT	PCT/EP09/67330	WO2010/079064	12/16/09	07/15/2010	Nationalized	Polyera and BASF
PF61582	EP	08172061.7		12/18/08		Abandoned?	Polyera and BASF
POL-202B CROSSLINKABLE DIELECTRICS AND METHODS OF PREPARATION AND USE THEREOF – <i>Kastler et al.</i>							
PF62169	PCT	PCT/EP10/056983	WO2010/136385	05/20/10	12/02/10	Pending	Polyera and BASF
PF62169	TW			05/20/10		Pending	Polyera and BASF
PF62169	EP	09160980.0		05/25/09		Pending	Polyera and BASF
POL-203B FUSED BITHIOPHENE-VINYLENE POLYMERS – <i>Kastler et al.</i>							
PF62202	PCT	PCT/EP10/057225	WO2010/149451	06/05/10	12/29/10	Pending	Polyera and BASF
PF62202	TW			06/05/10		Pending	Polyera and BASF
PF62202	EP	10150780.4		01/14/10		Pending	Polyera and BASF
PF62202	USPR	61/305,558		02/18/10		Expired	Polyera and BASF
PF62202	EP	09162087.2		06/05/09		Abandoned?	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
POL-204B							
FUSED SYSTEM-IMIDE SEMICONDUCTING COMPOUNDS AND POLYMERS – Usta et al.							
PF70549	US	13/095,517		04/27/11		Pending	Polyera and BASF
PF70549	PCT	PCT/IB11/051669		04/18/11		Pending	Polyera and BASF
PF70549	USPR	61/317,760		03/26/10		Expired	Polyera and BASF
POL-205B							
PERYLENE-BASED SEMICONDUCTORS AND METHODS OF PREPARATION AND USE THEREOF – Facchetti et al.							
PF70669	USPR	61/428,668		12/30/10		Pending	Polyera and BASF
POL-206B							
NAPHTHALENE-IMIDE SEMICONDUCTING COPOLYMERS WITH CYANATED COMONOMERS – Facchetti et al.							
PF70670	USPR	61/380,914		09/08/10		Pending	Polyera and BASF
POL-207B							
SEMICONDUCTOR MATERIALS /PREPARED FROM BRIDGED BITHIAZOLE COPOLYMERS – Mishra et al.							
PF71199	EP	10172083.7		08/05/10		Pending	Polyera and BASF
PF71199	USPR	61/370,857		08/05/10		Pending	Polyera and BASF
POL-208B							
N,N-DISUBSTITUTED NAPHTHALENEDIIMIDE-ETHYLENE-OLIGOETHIOPHENE-ETHYLENE-POLYMERS							
	EP					To be filed	Polyera and BASF
POL-209B							
NAPHTHALENEDIIMIDE-COPOLYMERS WITH BETTER AMBIENT STABILITY							
	USPR					To be filed	Polyera and BASF

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
NWU-001	PERYLENE N-TYPE SEMICONDUCTORS AND RELATED DEVICES - Marks et al.						
	US	11/043,814	7,671,202	01/26/05	03/02/10	Issued	Northwestern University
	USDV	12/648,484	7,982,039	12/29/09	07/19/11	Issued	Northwestern University
	Canada	2,554,302		01/26/05		Pending	Northwestern University
	China	200580003181.2	CN1980791A	01/26/05	06/13/07	Pending	Northwestern University
	Europe	05726476.4	1749316	01/26/05	02/07/07	Pending	Northwestern University
	Japan	2006-551415		01/26/05		Pending	Northwestern University
	Korea	10-2006-7017223	10-2007-0014125	01/26/05	01/31/07	Pending	Northwestern University
	PCT	PCT/US05/02385	WO2005/076815	01/26/05	08/25/05	Nationalized	Northwestern University
	USPR	60/539,133		01/26/04		Expired	Northwestern University
NWU-002	CARBONYL-FUNCTIONALIZED THIOPHENE COMPOUNDS AND RELATED DEVICE STRUCTURES - Marks et al.						
	US	11/043,814	7,528,176	09/14/05	05/05/09	Issued	Northwestern University
	USDV	12/432,063	7,964,650	04/29/09	06/21/11	Issued	Northwestern University
	Canada	2,579,407		09/14/05		Abandoned	Northwestern University
	China	200580038781.2	CN101056873A	09/14/05	10/17/07	Abandoned	Northwestern University
	Europe	05820820.8	1831205	09/14/05	09/12/07	Abandoned	Northwestern University
	Japan	2007-543027	2008-513544	09/14/05	05/01/08	Abandoned	Northwestern University
	Korea	10-2007-7008413		09/14/05		Abandoned?	Northwestern University
	PCT	PCT/US05/32833	WO2007/050049	09/14/05	05/03/07	Nationalized	Northwestern University
	USPR	60/609,678		09/14/04		Expired	Northwestern University

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
NWU-003	SILOXANE-POLYMER DIELECTRIC COMPOSITIONS AND RELATED ORGANIC FIELD-EFFECT TRANSISTORS - Marks et al.						
	US	11/315,076	7,605,394	12/22/05	10/20/09	Issued	Northwestern University
	USC1	12/562,800		09/18/09		Pending	Northwestern University
	EP	05857176.1	1839339	12/22/05	10/03/07	Pending	Northwestern University
	PCT	PCT/US05/46566	WO2006/086082	12/22/05	08/17/06	Nationalized	Northwestern University
	USPR	60/638,862		12/23/04	Expired	Northwestern University	
NWU-004	SILOLE-CONTAINING π -CONJUGATED POLYMERS, SYNTHESIS AND APPLICATION IN FIELD-EFFECT DEVICES - Marks et al.						
	US	11/803,020	7,605,225	05/11/07	10/20/09	Issued	Northwestern University
	USC1	12/563,680	7,816,480	09/21/09	10/19/10	Issued	Northwestern University
	Japan	2009-509886	2009-536980	05/11/07	10/22/09	Pending	Northwestern University
	USC2	12/888,922		09/23/10		Abandoned	Northwestern University
	Europe	07756255.1	2016594	05/11/07	01/21/09	Abandoned	Northwestern University
	PCT	PCT/US07/11451	WO2007/133705	05/11/07	11/22/07	Nationalized	Northwestern University
	USPR	60/799,520		05/11/06	Expired	Northwestern University	
NWU-005	CYANATED DIIMIDE SEMICONDUCTORS - Marks et al.						
	US	11/811,902	7,569,693	06/12/07	08/04/09	Issued	Northwestern University
	PCT	PCT/US07/13724	WO2007/146250	06/12/07	12/21/07	Abandoned	Northwestern University
	USPR	60/812,745		06/12/06		Expired	Northwestern University
NWU-006	CROSSLINKED POLYMERIC DIELECTRIC COMPOSITIONS AND METHODS OF MANUFACTURING AND USE THEREOF - Marks et al.						
	USDV	12/763,495		04/20/10		Pending	Northwestern University
	US	11/823,859	2008/0161464	06/28/07	07/03/08	Abandoned	Northwestern University
	PCT	PCT/US07/15147	WO2008/002660	06/28/07	01/03/2008	Abandoned	Northwestern University
	USPR	60/816,952		06/28/06		Expired	Northwestern University

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
NWU-007							SEMICONDUCTOR SILOXANE MATRICES FOR USE IN ORGANIC FIELD-EFFECT TRANSISTORS - Marks et al.
	US	11/957,911	2010/0038630	10/22/07	02/18/2010	Pending	Northwestern University
	PCT	PCT/US07/22416	WO2008/066622	10/22/07	06/05/2008	Abandoned	Northwestern University
	USPR	60/853,247	-----	10/22/06	-----	Expired	Northwestern University
NWU-008							CONJUGATED MONOMERS AND POLYMERS AND PREPARATION AND USE THEREOF - Marks et al.
	US	12/221,123	7,928,249	07/31/2008	04/19/2011	Issued	Northwestern University
	EP	08794934.3	2185496	07/31/2008	05/19/2010	Pending	Northwestern University
	JP	2010-519928	-----	07/31/2008	-----	Pending	Northwestern University
	PCT	PCT/US08/09268	WO2009017798	07/31/2008	02/05/2009	Nationalized	Northwestern University
	USPR	60/963,087	-----	08/02/2007	-----	Expired	Northwestern University
NWU-010							SOLUTION-PROCESSED HIGH MOBILITY INORGANIC THIN-FILM TRANSISTORS - Marks et al.
	US	12/322,399	2009/0206341	02/02/09	-----	Pending	Northwestern University
	EP	09706914.0	2245669	02/02/09	11/03/2010	Pending	Northwestern University
	JP	2010-545028	-----	02/02/09	-----	Pending	Northwestern University
	KR	10-2010-7019318	10-2010-0120295	02/02/09	11/15/2010	Pending	Northwestern University
	PCT	PCT/US09/00649	WO2009097150	02/02/09	08/06/2009	Nationalized	Northwestern University
	USPR	61/189,351	-----	08/18/08	-----	Expired	Northwestern University
	USPR	61/063,089	-----	01/31/08	-----	Expired	Northwestern University
NWU-011							POLYMERIC SEMICONDUCTORS AND RELATED DEVICES - Marks et al.
	US	12/827,146	-----	06/30/2010	-----	Pending	Northwestern University
	USPR	61/622,257	-----	07/01/2009	-----	Expired	Northwestern University

Ref. No.	Country	App. No.	Patent or Pub. No.	Filing Date	Pub. Date	Status	Assignee(s)
NWU-013		CONJUGATED POLYMERS AND DEVICES INCORPORATING SAME – <i>Facchetti et al.</i>					
	US	13/048,603		03/15/11		Pending	Polyera and Northwestern University
	PCT	PCT/US11/28523		03/15/11		Pending	Polyera and Northwestern University
	USPR	61/317,607		03/25/10		Expired	Polyera and Northwestern University
NWU-014		ORGANIC-INORGANIC HYBRID MULTILAYER GATE DIELECTRICS FOR THIN-FILM TRANSISTORS – <i>Marks et al.</i>					
	US	13/111,699		05/19/11		Pending	Northwestern University
	PCT	PCT/US11/37199		05/19/11		Pending	Northwestern University
	USPR	61/346,250		05/19/10		Expired	Northwestern University
NWU-016		CROSSLINKED HYBRID GATE DIELECTRIC MATERIALS AND ELECTRONIC DEVICES INCORPORATING SAME – <i>Marks et al.</i>					
	US	13/111,545		05/19/11		Pending	Northwestern University
	USPR	61/346,245		05/19/10		Expired	Northwestern University
NWU-018		LOW-TEMPERATURE FABRICATION OF NANOMATERIAL-DERIVED METAL COMPOSITE THIN FILMS – <i>Facchetti et al.</i>					
	USPR	61/502,644		06/29/11		Pending	Polyera and Northwestern University
NU21049		N-TYPE THIOPHENE SEMICONDUCTORS – <i>Marks et al.</i>					
	US	09/915,206	6,585,914	07/24/01	07/01/2003	Issued	Northwestern University
	US	10/610,276	6,991,749	06/30/03	01/31/2006	Issued	Northwestern University
	US	11/343,407	7,374,702	01/31/06	05/20/2008	Issued	Northwestern University
	US	12/113,662	7,842,198	05/01/08	11/30/2010	Issued	Northwestern University
	US	12/927,896	2011-0118483	11/29/10	05/19/2011	Pending	Northwestern University
	USPR	60/751,861		07/24/00		Expired	Northwestern University
NU20024		N-TYPE THIOPHENE SEMICONDUCTORS – <i>Marks et al.</i>					
	US	09/915,210	6,608,323	07/24/01	08/16/2006	Issued	Northwestern University

Trademarks

Registered Trademarks

<u>Debtor/ Obligor</u>	<u>Mark</u>	<u>Filing Date/Registration Date</u>	<u>Status</u>	<u>Application/ Registration No.</u>
Polyera Corporation	Activink	September 1, 2009	Registered	3,677,029
Polyera Corporation	Activinks	September 1, 2009	Registered	3,677,030
Polyera Corporation	Polyera	September 1, 2009	Registered	3,677,030

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